

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>	Docket number (Optional) <b>15689.49.4</b>	Application Number <b>10/673,940</b>
	Applicant(s) <b>Takehiro Nakamura et al.</b>	
	Filing Date <b>September 29, 2003</b>	Group Art Unit <b>2611</b>

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

U.S. PATENT APPLICATION PUBLICATIONS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
	1	0 682 418 A2	05/12/1995	EPO	H0487	005	X	
	2	CN1126930	7/17/1996	China	H04B7	005	X	

EXAMINER	DATE CONSIDERED
----------	-----------------

**EXAMINER:** Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>	<b>Docket number (Optional)</b> <b>15689.49.4</b>	<b>Application Number</b> <b>10/673,940</b>
	<b>Applicant(s)</b> <b>Takehiro Nakamura et al.</b>	
	<b>Filing Date</b> <b>September 29, 2003</b>	<b>Group Art Unit</b> <b>2611</b>

*Examiner Initial	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
	3	Chinese Office Action for Chinese Patent Application No.: 20031010330.1
EXAMINER		DATE CONSIDERED
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.		